



L	Hits	Search Text	DB	Time stamp
Number				2002/11/23
1	48	plasma and (RF or radiofrequency) and	USPAT;	12:33
		impedance and capacitors and resistor and	EPO; JPO;	12:33
		"matching circuit"	IBM_TDB USPAT;	2002/11/23
5	1381	plasma and (RF or radiofrequency) and	EPO; JPO;	12:38
		impedance and capacitors	1	12:30
6	28205	resistor same "voltage drop"	IBM_TDB	2002/11/23
			USPAT;	10:59
			EPO; JPO; IBM TDB	10.59
8	619	plasma and (RF or radiofrequency) and	USPAT;	2002/11/23
				11:03
		impedance and capacitors and resistor	EPO; JPO; IBM TDB	11.03
	1	11.5	USPAT;	2002/11/23
9	372	(plasma and (RF or radiofrequency) and		12:21
		impedance and capacitors and resistor)	EPO; JPO; IBM TDB	12.21
11	35	and etch\$5 (plasma and (RF or radiofrequency) and	USPAT;	2002/11/23
			1	12:21
		impedance and capacitors and resistor)	EPO; JPO; IBM TDB	12.21
		and endpoint	USPAT;	2002/11/23
12	12	plasma same (RF or radiofrequency) same	EPO; JPO;	12:35
13		("matching-circuit" near4-voltage)	IBM TDB	1.6.0.0.0
		11 6	USPAT;	2002/11/23
	222	plasma and (RF or radiofrequency) and	EPO; JPO;	12:38
		impedance and capacitors and (resistor	IBM TDB	12.30
		near4 voltage)	I DEL TOB	